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Status of pixel sensor prototypes for the CEPC vertex detector

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On behalf of the pixel sensor design teams

2022-5-23

Joint Workshop of the CEPC Physics, Software and New Detector
Concept in 2022

Outline

- **Overview of pixel sensors developed for CEPC VTX**
- **Progress of the JadePix chips**
- **Progress of the TaichuPix chips**
- **Progress of the SOI-3D chips**
- **Summary and outlook**

CEPC Vertex detector requirements

Circular Electron Positron Collider (CEPC) proposed as a Higgs factory.

- **Efficient tagging of heavy quarks (b/c) and τ leptons**

→ Impact parameter resolution,

$$\sigma_{r\phi} = 5 \oplus \frac{10}{(p \cdot \sin^{3/2}\theta)} (\mu m)$$

Physics driven requirements

$\sigma_{s.p.}$ **2.8 μm**

Material budget **0.15% X_0 /layer**

r of Inner most layer **16 mm**

Running constraints

Air cooling

beam-related background

radiation damage

Sensor specifications

Small pixel **~16 μm**

Thinning to **50 μm**

low power **50 mW/cm²**

fast readout **~1 μs**

radiation tolerance

≤ 3.4 Mrad/ year

$\leq 6.2 \times 10^{12} n_{eq}/(cm^2 \text{ year})$

Baseline design parameters for CEPC vertex detector

	R (mm)	z (mm)	\cos \theta	σ (μm)
Layer 1	16	62.5	0.97	2.8
Layer 2	18	62.5	0.96	6
Layer 3	37	125.0	0.96	4
Layer 4	39	125.0	0.95	4
Layer 5	58	125.0	0.91	4
Layer 6	60	125.0	0.90	4

Ref: CEPC Conceptual Design Report, Volume II - Physics & Detector, <http://cepc.ihep.ac.cn/>

Overview of pixel sensors in China for CEPC VTX

■ Development of pixel sensors for CEPC VTX supported by

- Ministry of Science and Technology of China (MOST)
- National Natural Science Foundation of China (NSFC)
- IHEP fund for innovation

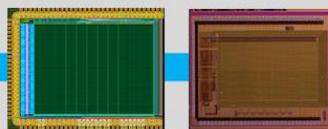
This talk

2015



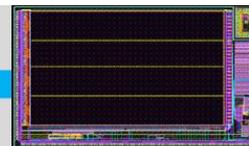
JadePix-1

2017



JadePix-2/MIC4

2019

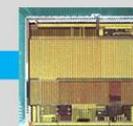


JadePix-3

2020

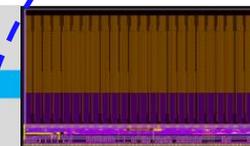


TaichuPix-1

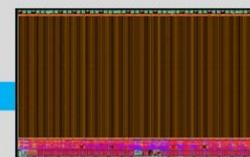


TaichuPix-2

2021



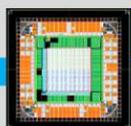
JadePix-4/MIC5



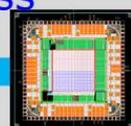
TaichuPix full scale

180nm CIS process

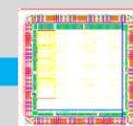
200nm SOI process



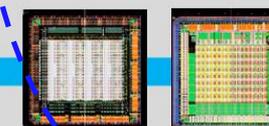
CPV-1



CPV-2



CPV-3



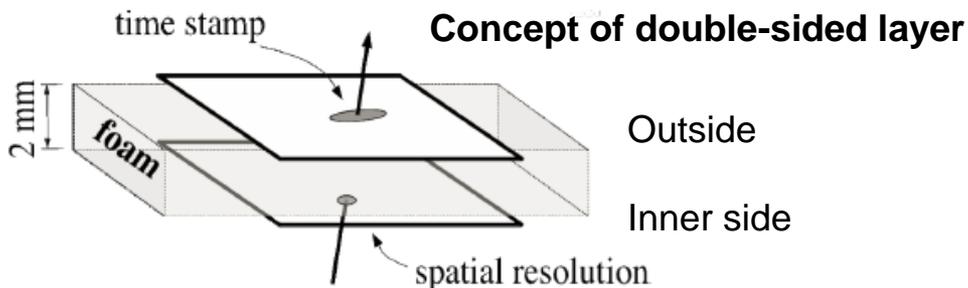
CPV-4

Ref: "Status report on MAPS in China", 2021 CEPC workshop, Yunpeng Lu

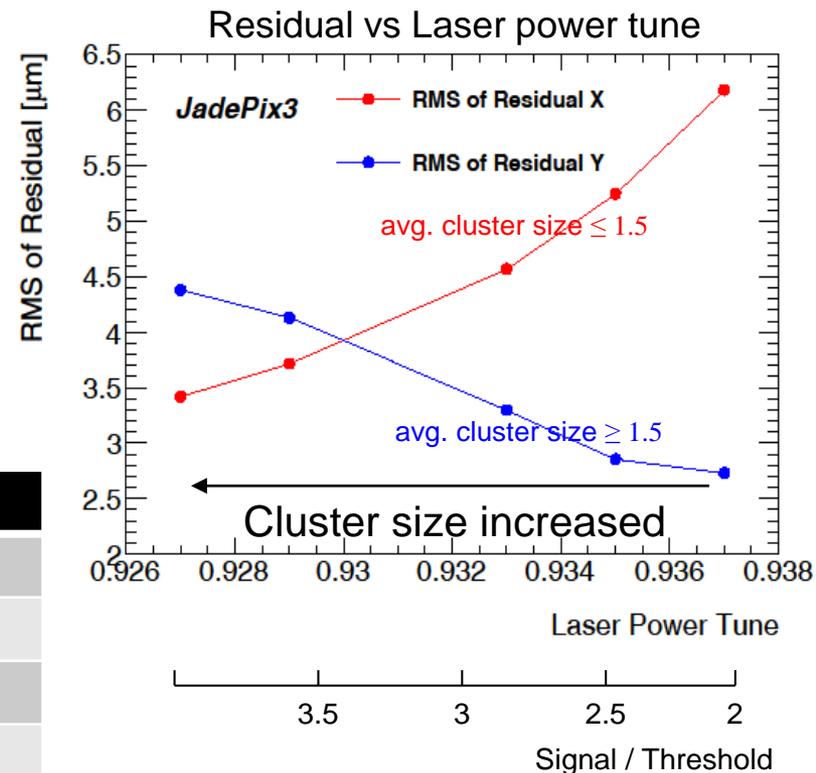
Update on JadePix chips

■ JadePix concerns the concept of double-sided layer

- Fine pitch & low power sensor for spatial resolution
 - Laser test on JadePix-3 indicates **s.p. < 3 μm achievable**
- A faster sensor to provide time-stamp
 - **JadePix-4 in fabrication**



	JadePix-3	JadePix-4/MIC5
Pixel size	16 μm × 23.1 μm	20 μm × 29 μm
Integration time	98.3 μs	~ 1 μs
Average power	< 100 mW/cm ²	< 100 mW/cm ²
Pixel array	512 row × 192 col.	356 row × 498 col.
Die size	10.4 mm × 6.1 mm	14.8 mm × 8.6 mm
Readout mode	Rolling shutter	Data-driven



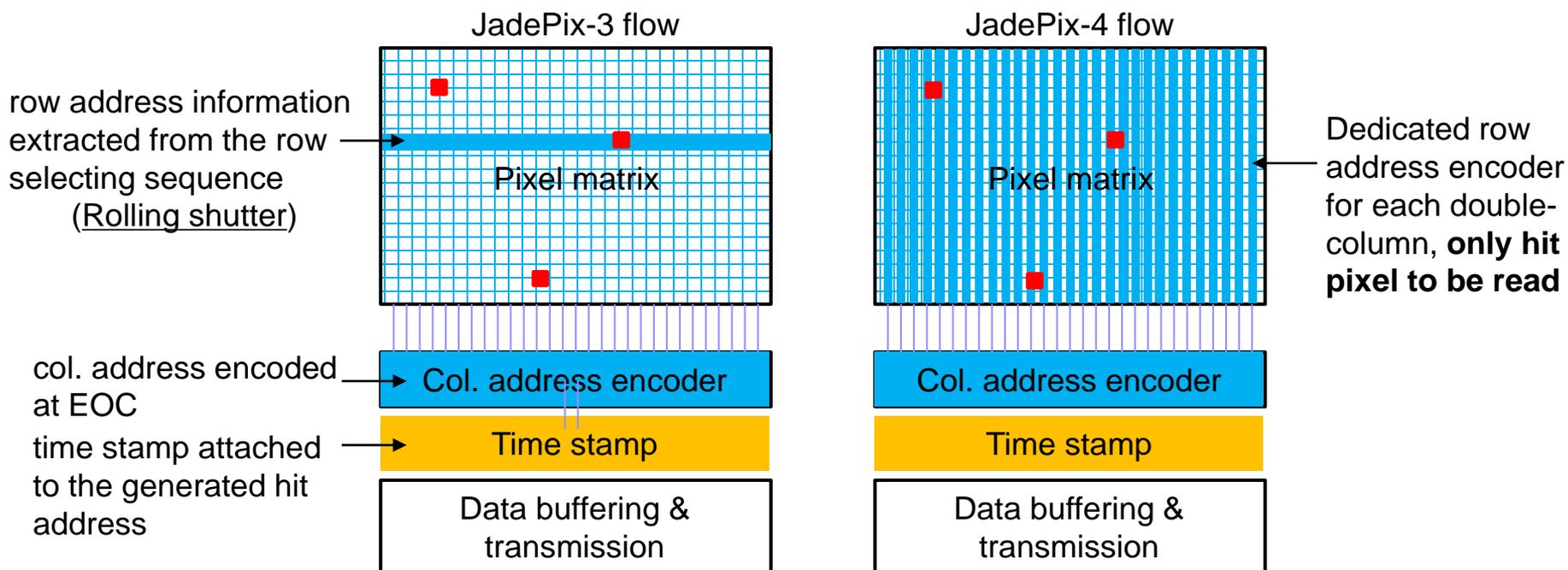
Hit processing flow of JadePix-3/4

- Hit registered in each pixel needs fast processing

- Hit position (col. and row address) to be encoded
- Time stamp to be attached
- Register to be reset for the next hit

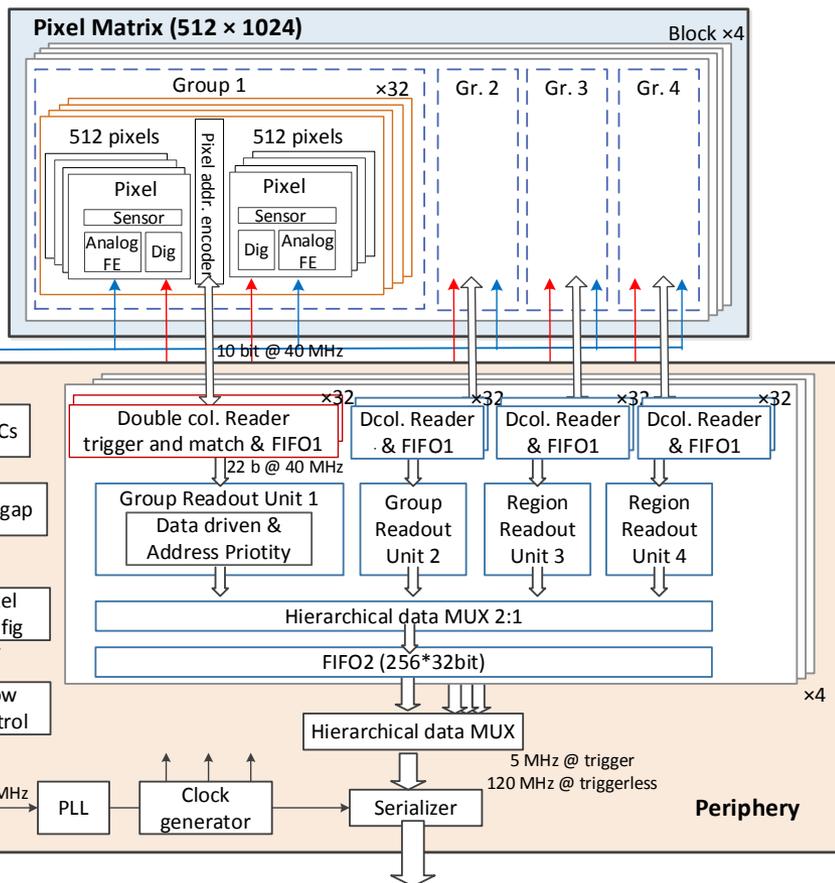
- A major modification on the hit processing flow

- Row address encoding embedded into the active pixel matrix, which is much faster



TaichuPix architecture

Motivation: a large-scale & full functionality pixel sensor for the first 6-layer vertex detector prototype



- **Pixel 25 μm × 25 μm**
 - Continuously active front-end, in-pixel discrimination
 - Fast-readout digital, with masking & testing config. logic
- **Column-drain readout for pixel matrix**
 - Priority based data-driven readout
 - **Time stamp added at EOC**
 - **Readout time: 50 ns** for each pixel
- **2-level FIFO architecture**
 - L1 FIFO: de-randomize the injecting charge
 - L2 FIFO: match the in/out data rate between core and interface
- **Trigger-less & Trigger mode compatible**
 - Trigger-less: 4.48 Gbps data interface
 - Trigger: data coincidence by time stamp, only matched event will be readout
- **Features standalone operation**
 - On-chip bias generation, LDO, slow control, etc.

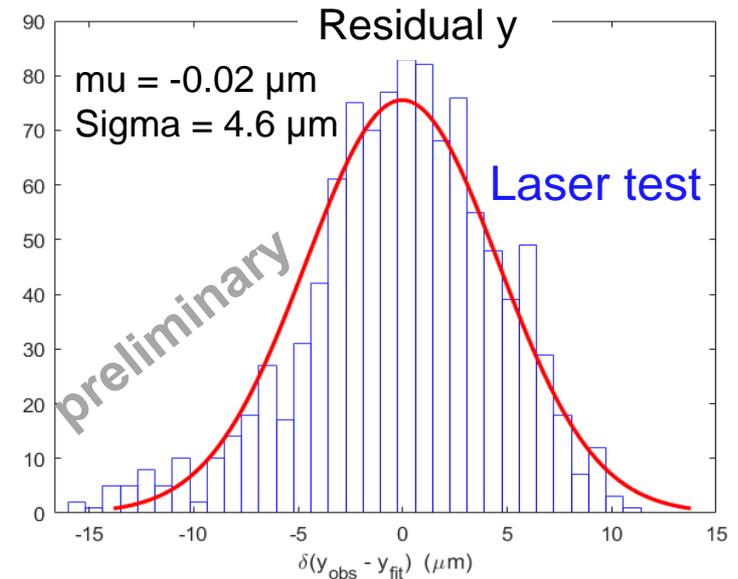
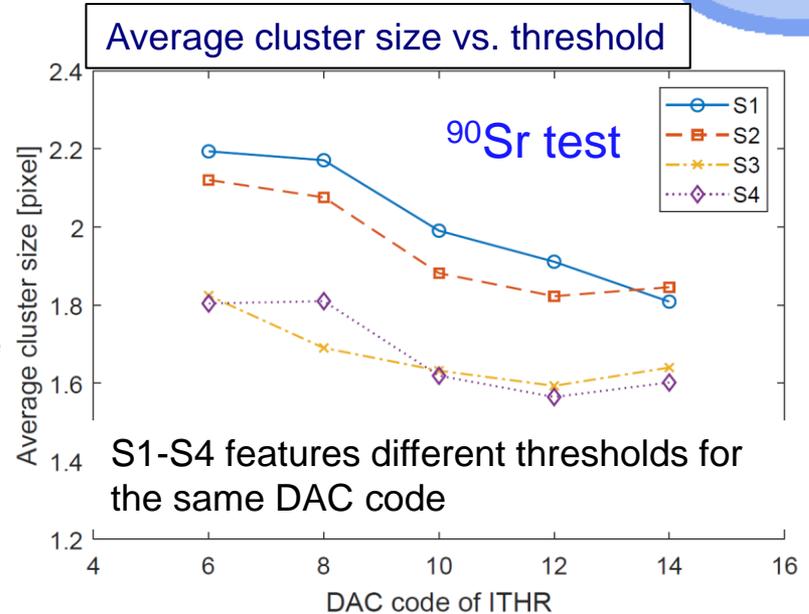
Update on TaichuPix chips

■ TaichuPix2 test with ^{90}Sr

- Average cluster size decreases with threshold as expected
- **Cluster size < 3** indicates the estimated maximum hit rate (36 MHz/cm²) reasonable
- **Cluster size > 1** could benefit the spatial resolution (better than $\text{pitch}/\sqrt{12} = 7.2 \mu\text{m}$)

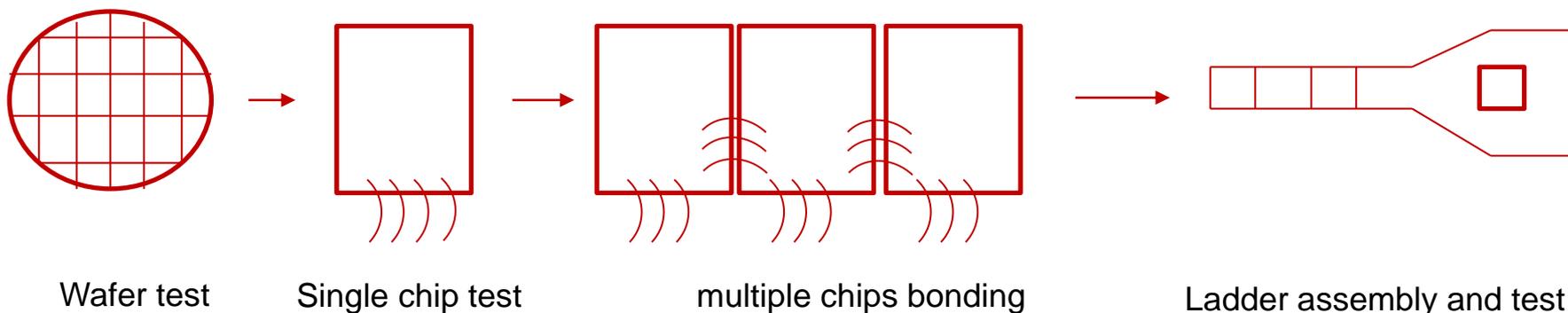
■ Laser test

- Laser diode with 658 nm wavelength
- One dimension laser scan on the test chip with fixed step of 1 μm
- Preliminary result indicates a resolution **less than 5 μm**
- Further investigation ongoing
 - Laser 1064 nm
 - With different laser power and/or diff. pixel threshold



Update on TaichuPix chips

- **First full-scale prototype in fabrication, to be received in June**
 - Die size 25.7 mm × 15.9 mm
 - Pixel cell inherited from MPW + scaled logic with new layout Periphery + debugged/improved blocks + enhanced power network
 - 12 wafers ordered, expected to be assembled on the ladder prototype
- **Preparation for chip & ladder test in progress**
 - Probe card customized for the wafer test
 - Single chip test board designed and fabricated
 - Ladder readout electronics and DAQ designed



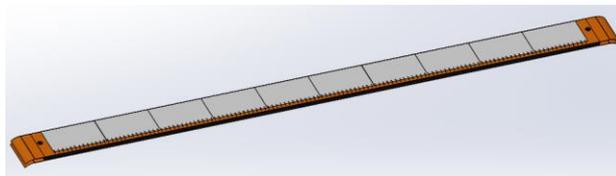
Ladder readout design

- **Detector ladder required for detector assembly**
 - Sensor chips, readout electronics, mechanical support, etc.

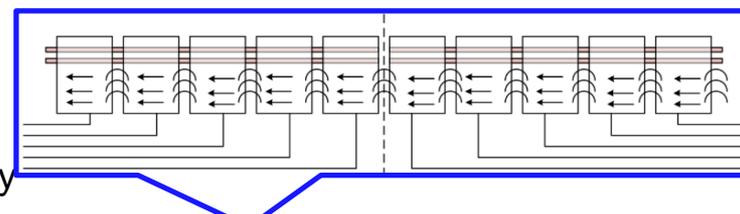
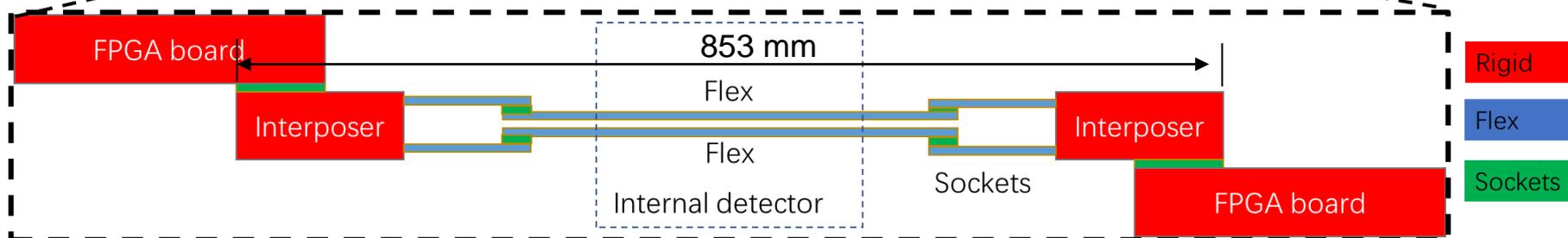
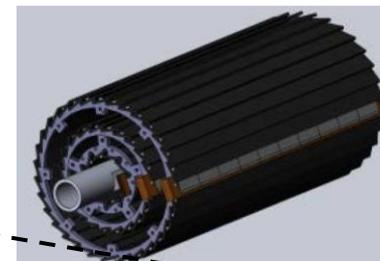
CMOS imaging sensor prototype



Detector module (ladder) prototype



Full size vertex detector Prototype



- **Ladder readout structure**

- Containing 3 boards for easier production & assembly
 - Flex board: Assembled with 10 TaichuPix chips, **dual sides readout**
 - Interposer board: FMC mezzanine rigid and flex board, in production
 - FPGA board: FMC carrier board, available in the lab

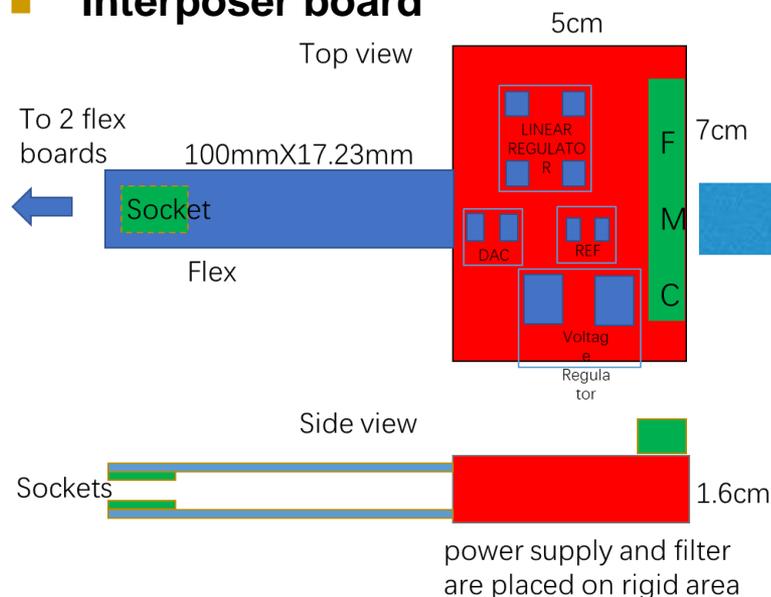
Ladder readout design

Two versions of flex board designed

- Version 1 (baseline): 2 layers, **less material**, limited layout space leads to **worse signal integrity**, thickness ~0.2 mm, in production
- Version 2: 4 layers, **more material** dedicated GND and power plane gain **better signal integrity**, thickness ~0.4 mm, production done



Interposer board



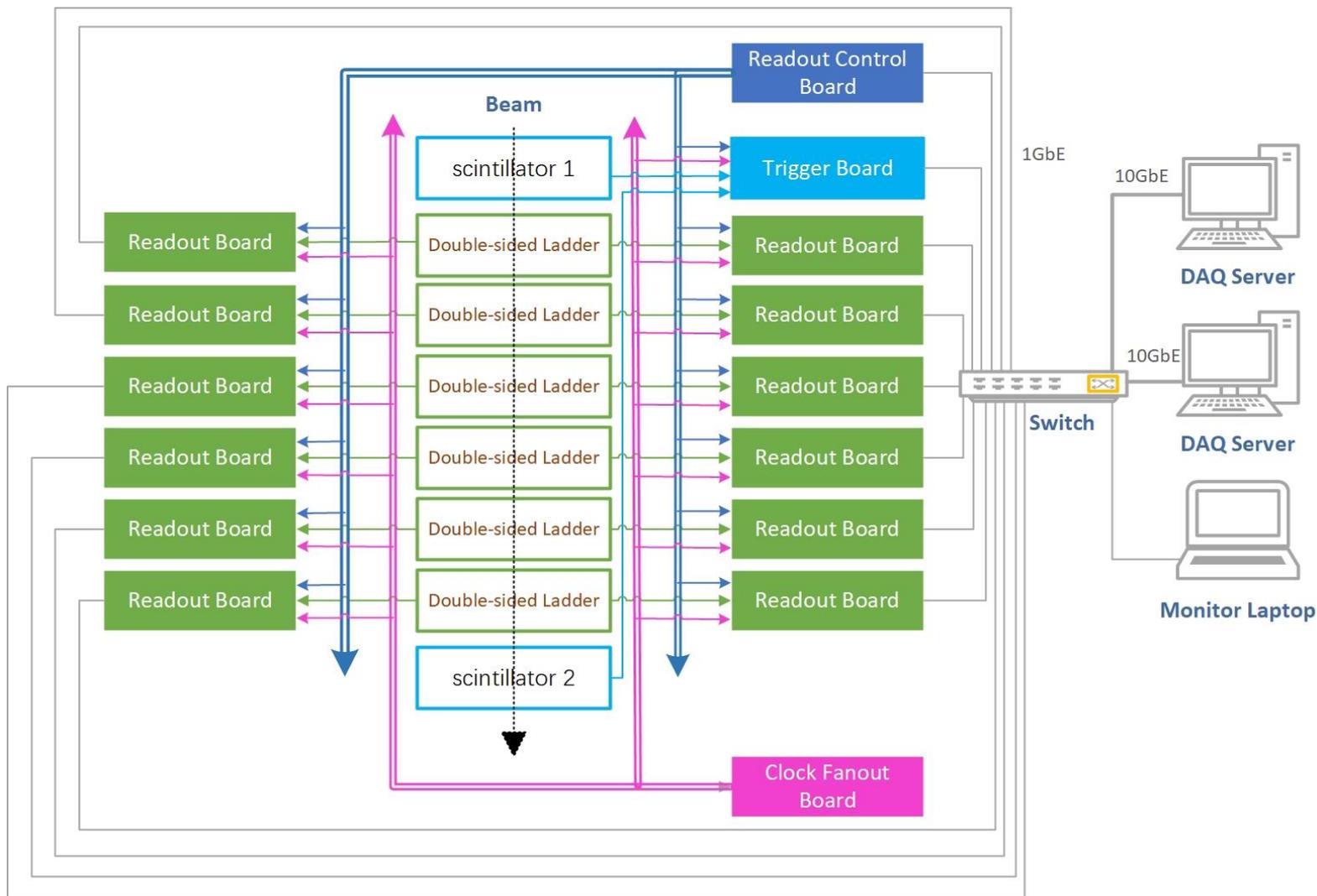
FPGA board



- Communication with chips
- Data processing and package data
- Readout to PC via 1Gbps Ethernet
- Capability of 6 Gbps readout and 2GB internal DDR memory

Design of DAQ

- Considering 6 double-sided ladders

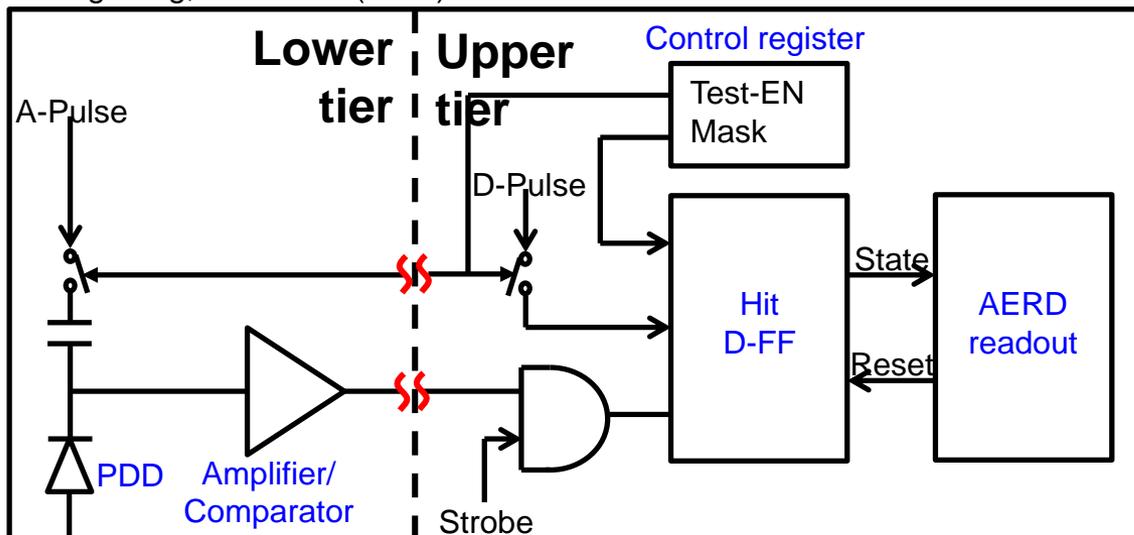


Status of SOI prototypes

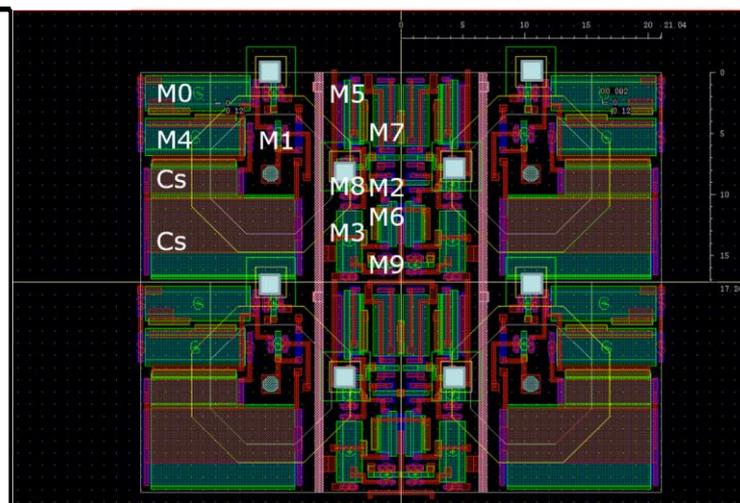
Exploring the 3D technology on CPV4 design

- **2 tiers to accommodate the full-functioned pixel: $17.24 \times 21.04 \mu\text{m}^2$ on each**
 - Lower tier: PDD (Pinned Depleted Diode) sensing diode + amplifier/comparator
 - Upper tier: Hit D-Flipflop + Control register + AERD readout*
- **2 vertical connections in each pixel: comparator output and test switch**
 - Power / ground connection implemented in the I/O pad ring
- **Critical to make the PDD and analog front-end compatible**
 - $V_{\text{thr.}}$ shift by -70 mV/PMOS, 50 mV/NMOS as the PDD depleted (-4 V)

*Ping Yang, NIMA 785 (2015) 61-69



3D bumps marked with 

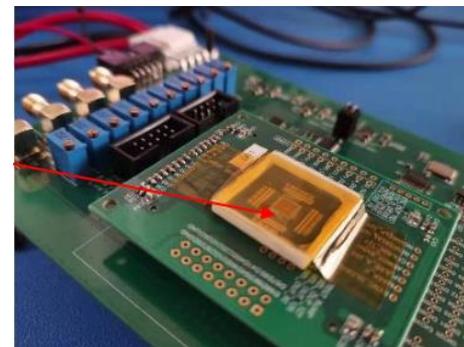


4 pixels arranged in 2 columns

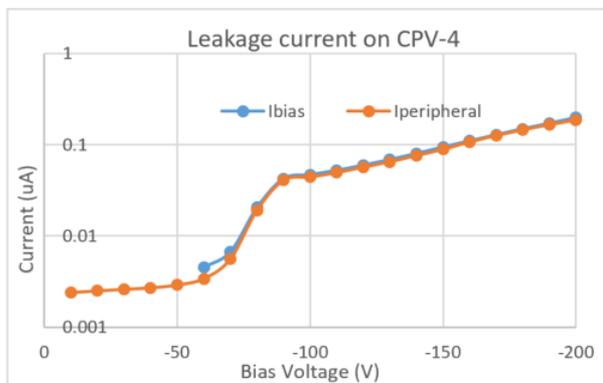
Status of SOI prototypes

Functional verification of CPV-4 before 3D integration

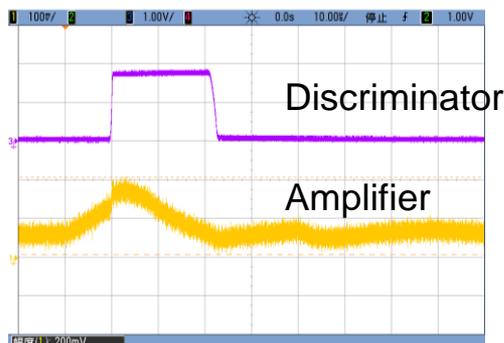
- **Quick test on the Lower and upper tier separately**
 - Checkpoint before the 3D integration
- **Leakage current reduced successfully by**
 - Optimization of PDD implant dose
 - 1 Bias Ring + 4 Guard Ring + 1 Current Collecting Ring
- **Analog front-end operated with the PDD sensor**
 - Analog waveform inspected on oscilloscope
- **Digital logic functions validated**



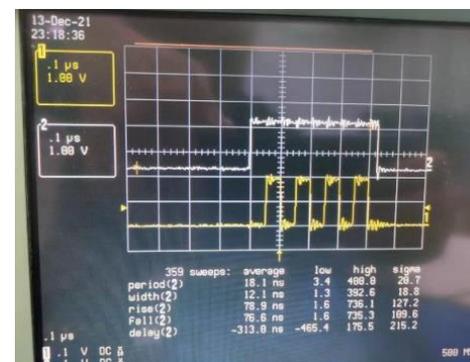
CPV4 digital sensor bonded on test board



The analog sensor can be biased at -200 V



Analog frontend with PDD
Test charge injected $\sim 750 e^-$



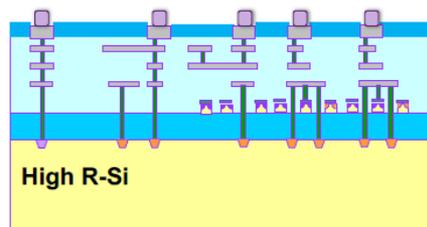
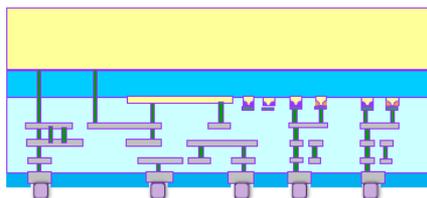
Pulse injection test of digital sensor
white line: valid signal, representing hit occurs
Yellow line: reset signal after read the pixel

SOI-3D integration ongoing

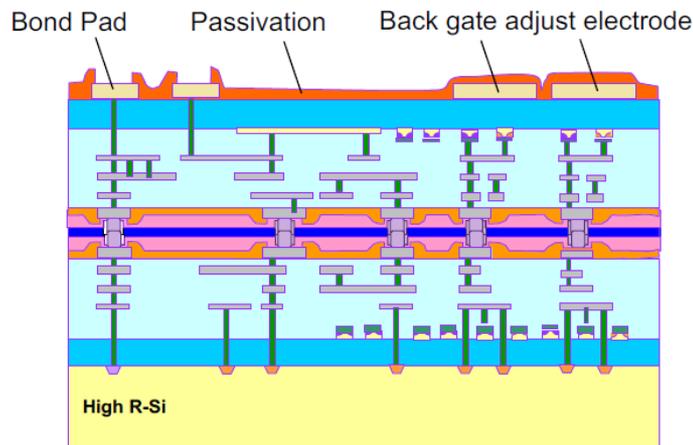
■ 3D integration by foundry in Japan in progress

- The bulk of upper tier removed by wet-etching
 - 260 μm \rightarrow 10 μm thick
 - Lower tier can be thinned as a conventional sensor
 - 75 μm in SOI case and 50 μm in CMOS case (lower tier not necessarily an SOI sensor)
- * Currently SOI-3D demonstrated on a lower tier of 260 μm thick

Upper Chip



Lower Chip



CPV-4 (3D) expected available in August

■ Test and DAQ system being developed

Summary and outlook

■ Progress made on the JadePix and TaichuPix development

- JadePix-4 featuring a fast readout designed as a complementary to the JadePix-3, in fabrication
- The first full-scale TaichuPix prototype designed based on the TaichuPix-2 results, in fabrication
- The Ladder assembled with TaichuPix chips being designed
 - Readout electronics, DAQ, mechanics, etc.
- 6 double-sided ladder expected available in November
- Beam test @ DESY planned in December

■ Exploration of SOI-3D has started with the first design of CPV4-3D

- Targeting on the full specs of pixel sensors
- To examine the scheme, implementation and yield of SOI-3D
- Quick test on the Lower and upper tier separately
 - Functionality verification done, promising result obtained
- 3D-integration prototype expected available in August
- 2 ~3 MPW run planned in 5 years

■ Exploration of next generation of CMOS pixel sensor technology ongoing

- A 55 nm CMOS technology provided by Chinese foundry is being evaluated

Pixel sensor teams

■ JadePix-3/4

- IHEP: Ying Zhang, Yang Zhou, Zhigang Wu (graduated), Jing, Dong, Wenhao Dong/ USTC, Chunhao Tian/ USTC, Yunpeng Lu, Qun Ouyang
- CCNU: Yang Ping, Weiping Ren, Le Xiao, Di Guo, Chenxing Meng (graduated), Anyang Xu (graduated), Sheng Dong, Hulin Wang, Xiangming Sun
- SDU: Liang Zhang
- Dalian Minzu Univ: Zhan Shi

■ TaichuPix

- IHEP: Wei Wei, Ying Zhang, Xiaoting Li, Jun Hu, Hongyu Zhang, Zhijun Liang, Joao Guimaraes da Costa
- CCNU/ IFAE: Tianya Wu, Raimon Casanova, Sebastian Grinstein
- NWPUP: Xiaomin Wei, Jia Wang
- SDU: Liang Zhang, Jianing Dong, Long Li

■ SOI

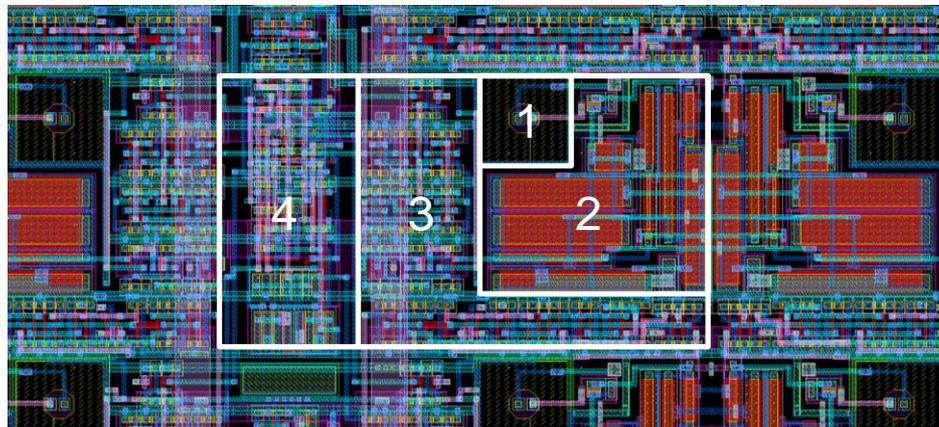
- IHEP: Yupeng Lu, Yang Zhou, Jia Zhou, Jing Dong, Mingyi Dong, Hongyu Zhang, Qun Ouyang

Thank you very much for your attention!

Backup slides

Design of JadePix-4/MIC5

- **Key component verified and reused from JadePix-3**
 - Diode
 - Analog frontend
 - Hit register
- **Asynchronized Encoder and Reset Decoder (AERD) ***
 - Generating col. and row address from hit pixel
 - Tracing back to reset hit pixel
- **Final layout of pixel matrix**
 - pixel array: 356 row \times 498 col.
 - Pixel size: 20 μm \times 29 μm



JadePix-4 pixel layout
(MET4 and above not shown)

1. Diode
2. Analog frontend
3. Digital logic
4. AERD shared by 2 col.

*P. Yang, etc., NIMA 785 (2015) 61-69

Layer Stackup



- Option1 (baseline)

- 2 layers
- Less material
- limited layout space lead to worse signal integrity
 - Crosstalk
 - Large voltage drop
 - Ground bounce
- Thickness: $\sim 0.2\text{mm}$ (+0.1mm stiffener)

Coverlay
50um
Copper
18um
Polyimide
50um
Copper
18um
Coverlay
50um
Stiffener
100um



- Option2

- 4 layers
- Dedicated GND and power plane gain better signal integrity
- More material
- Thickness: $\sim 0.38\text{mm}$ (+ 0.1mm stiffener)
- For study the ASIC chips and electronics performance

The design of the 2 options is similar, and the production has been started at the same time.